613 254 9222

Appl. No. 10/507,100 Amdt. dated December 30, 2005 Reply to Office action of September 30, 2005 Atry. Docket No. AP928USN

## Amendments to the Specification:

Please replace the paragraph beginning at page 3, line 15 with the following amended paragraph:

-- According to the present invention, a photosensitive material comprises at least one organic species in an organic-inorganic a host matrix, the at least one organic species comprising a material having a refractive index which changes upon exposure to actinic radiation, wherein the host matrix comprises a material formed by interpenetrating of inorganic and organically-modified networks. --

Please replace the paragraph beginning at page 4, line 1 with the following amended paragraph:

-- According to a second aspect of the invention, there is provided a process of making a photosensitive material comprising the steps of forming an organic-inorganic a host matrix containing at least one organic species having a refractive index that changes on exposure to actinic radiation, the host matrix being formed as interpenetrating networks of inorganic and organically-modified phases.